F. Silicon and Group-IV Devices and Integration Technology 분과 [TB1-F] Emerging Device Technology I

TB1-F-1 09:00~09:30	[초청] Optimization of Spacer and Source/Channel Junction to Improve TFET Characteristics Garam Kim ¹ and Sangwan Kim ² ¹ Myongji University, ² Ajou University
TB1-F-2 09:30~09:45	Switching Characteristics Analysis of Tunnel Field-effect Transistor with Elevated Drain by Changing Drain Underlap Length Changha Kim ¹ , Kitae Lee ¹ , Junil Lee ¹ , Ryoongbin Lee ¹ , Sihyun Kim ¹ , Hyun-min Kim ¹ , Sangwan Kim ² and Byung-Gook Park ¹ ¹ Inter-University Semiconductor Research Center (ISRC) and Department of Electrical and Computer Engineering, Seoul National University, ² Department of Electrical and Computer Engineering, Ajou University
TB1-F-3 09:45~10:00	Digital Inverter with Positive Feedback Field Effect Transistor Changhoon Lee and Changhwan Shin Department of Electrical and Computer Engineering, Sungkyunkwan University
TB1-F-4 10:00~10:15	A Novel Gate-normal Hetero-gate-dielectric (GHG) Tunnel Field-effect Transistors (TFETs) Jang Woo Lee and Woo Young Choi Department of Electronic Engineering, Sogang University
TB1-F-5 10:15~10:30	Capacitorless Double-Gate PNPN TFET 1T DRAM with SiGe Channel Jae Seung Woo and Woo Young Choi Department of Electronic Engineering, Sogang University